

<b>Notice of References Cited</b>	Application/Control No. 10/821,201		Applicant(s)/Patent Under Reexamination PANDA ET AL.	
	Examiner George A. Goudreau		Art Unit 1792	Page 1 of 1

#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
	C	US-			
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#### FOREIGN PATENT DOCUMENTS

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#### NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	"Magnetically enhanced Rie etching of submicron silicon trenches"; Proceedings of the SPIE (1991'); vol. 1392; pp. 253-264;Cooper et. al.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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